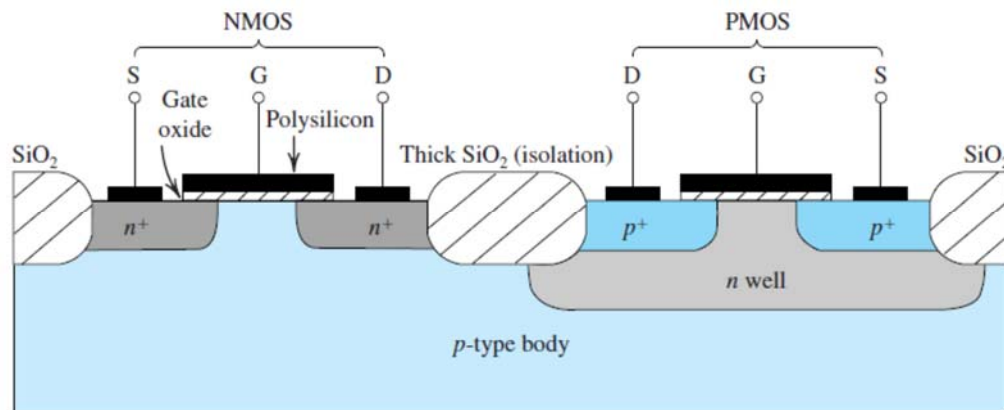


## Complementary MOS or CMOS:

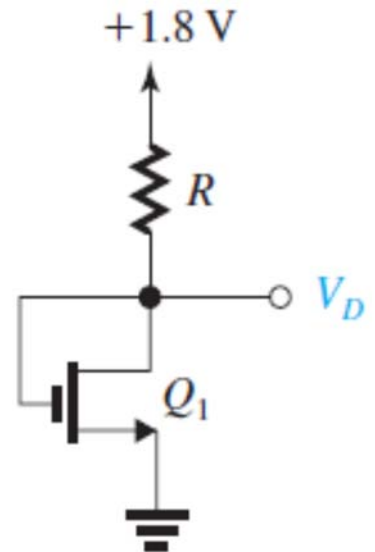


- As the name implies, complementary MOS technology employs MOS transistors of both polarities.
- Although CMOS circuits are somewhat more difficult to fabricate than NMOS, the availability of complementary devices makes possible many powerful circuit configurations.
- Figure above shows a cross section of a CMOS chip illustrating how the PMOS and NMOS transistors are fabricated.
- Observe that while the NMOS transistor is implemented directly in the  $p$ -type substrate, the PMOS transistor is fabricated in a specially created  $n$  region, known as an  $n$  well.
- The two devices are isolated from each other by a thick region of oxide that functions as an insulator.
- Not shown on the diagram are the connections made to the  $p$ -type body and to the  $n$  well. The latter connection serves as the body terminal for the PMOS transistor.

**Example:**

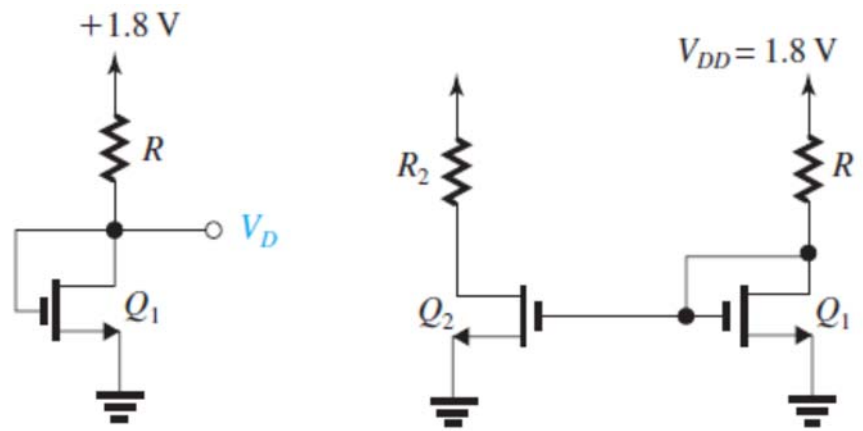
For the circuit in Fig. E5.9, find the value of  $R$  that results in  $V_D = 0.7\text{ V}$ . The MOSFET has  $V_{tn} = 0.5\text{ V}$ ,  $\mu_n C_{ox} = 0.4\text{ mA/V}^2$ ,  $W/L = \frac{0.72\text{ }\mu\text{m}}{0.18\text{ }\mu\text{m}}$ , and  $\lambda = 0$ .

**Solution:**



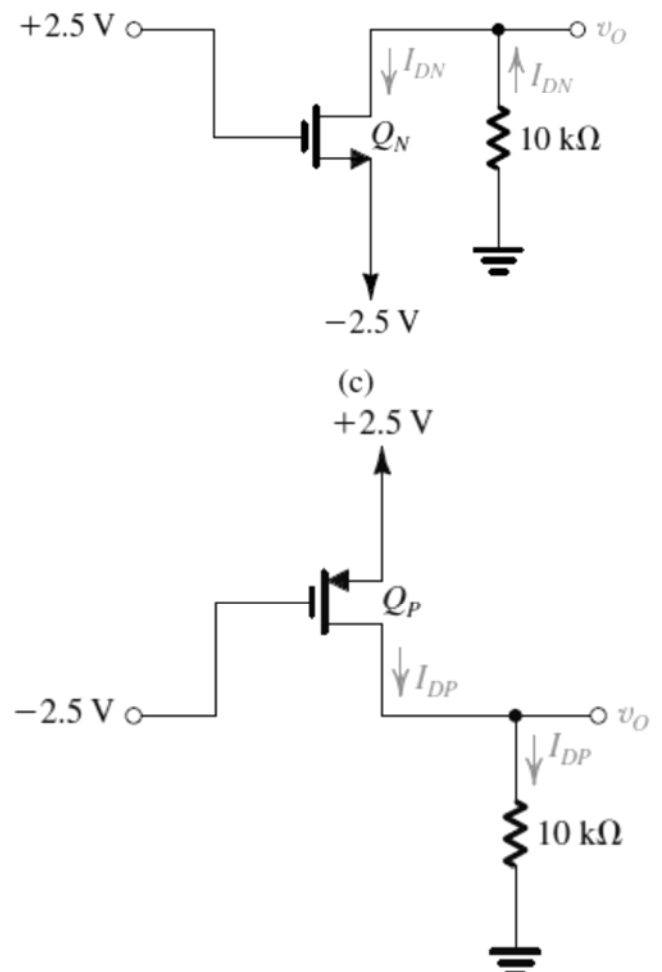
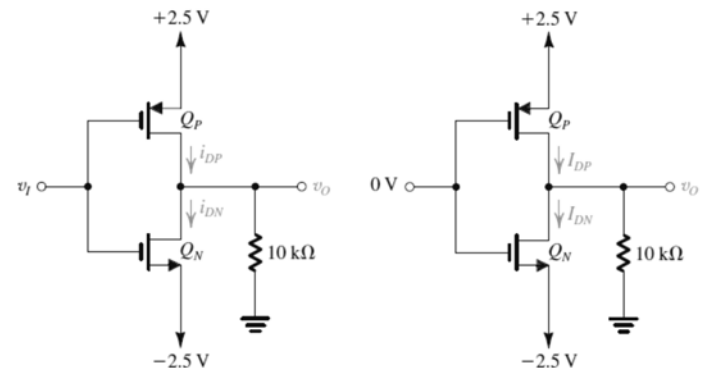
**Example:**

Figure E5.10 shows a circuit obtained by augmenting the circuit of Fig. E5.9 considered in Exercise 5.9 with a transistor  $Q_2$  identical to  $Q_1$  and a resistance  $R_2$ . Find the value of  $R_2$  that results in  $Q_2$  operating at the edge of the saturation region. Use your solution to Exercise 5.9.

**Solution:**

**Example:**

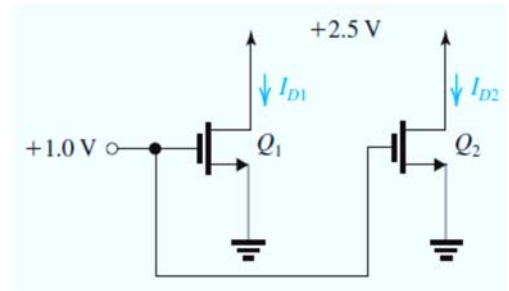
The NMOS and PMOS transistors in the circuit of Fig. 5.26(a) are matched, with  $k'_n(W_n/L_n) = k'_p(W_p/L_p) = 1 \text{ mA/V}^2$  and  $V_{tn} = -V_{tp} = 1 \text{ V}$ . Assuming  $\lambda = 0$  for both devices, find the drain currents  $i_{DN}$  and  $i_{DP}$ , as well as the voltage  $v_O$ , for  $v_I = 0 \text{ V}$ ,  $+2.5 \text{ V}$ , and  $-2.5 \text{ V}$ .

**Solution:**

**Example:**

**5.29** Figure P5.29 shows two NMOS transistors operating in saturation at equal  $V_{GS}$  and  $V_{DS}$ .

- (a) If the two devices are matched except for a maximum possible mismatch in their  $W/L$  ratios of 3%, what is the maximum resulting mismatch in the drain currents?
- (b) If the two devices are matched except for a maximum possible mismatch in their  $V_t$  values of 10 mV, what is the maximum resulting mismatch in the drain currents?  
Assume that the nominal value of  $V_t$  is 0.6 V.

**Solution:**

**Example:**

**D 5.32** In a particular IC design in which the standard channel length is  $1\text{ }\mu\text{m}$ , an NMOS device with  $W/L$  of 10 operating at  $200\text{ }\mu\text{A}$  is found to have an output resistance of  $100\text{ k}\Omega$ , about  $\frac{1}{5}$  of that needed. What dimensional change can be made to solve the problem? What is the new device length? The new device width? The new  $W/L$  ratio? What is  $V_A$  for the standard device in this IC? The new device?

**Example:**

**D 5.33** For a particular  $n$ -channel MOS technology, in which the minimum channel length is  $0.5\ \mu\text{m}$ , the associated value of  $\lambda$  is  $0.03\ \text{V}^{-1}$ . If a particular device for which  $L$  is  $1.5\ \mu\text{m}$  operates in saturation at  $v_{DS} = 1\ \text{V}$  with a drain current of  $100\ \mu\text{A}$ , what does the drain current become if  $v_{DS}$  is raised to  $5\ \text{V}$ ? What percentage change does this represent? What can be done to reduce the percentage by a factor of 2?